

Form 1449*	Atty. Docket No.: 303.311US2	Serial No. Unknown
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)	Applicant: Christophe Pierrat et al.	
	Filing Date: Herewith	Group: Unknown

U.S. PATENT DOCUMENTS

**Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
<i>26-2</i>	4,608,268	08/26/1986	Shimkunas, A.R.	427	8	07/23/85
<i>A</i>	4,653,860	03/31/1987	Hendrix, J.R.	350	336	01/07/85
	4,686,162	08/11/1987	Stangl, G., et al.	430	5	10/12/84
	5,045,419	09/03/1991	Okumura, K.	430	20	12/26/89
	5,047,117	09/10/1991	Roberts	156	643	03/26/90
	5,194,345	03/16/1993	Rolfson			05/14/91
	5,194,346	03/16/1993	Rolfson, et al.	430	5	04/15/91
	5,208,125	05/04/1993	Dowrey, et al.			07/30/91
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	5,229,872	07/20/1993	Mumola, P.B.	359	40	01/21/92
	5,240,796	08/31/1993	Lee, et al.			07/09/91
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	5,281,500	01/25/1994	Cathey, et al.	430	5	09/04/91
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	5,288,569	02/22/1994	Lin	430	5	04/23/92
	5,372,901	12/13/1994	Rolfson, et al.			08/05/92
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	5,565,286	10/15/1996	Lin, B.J.	430	005	11/17/94
	5,567,573	10/22/1996	Morton, S.G.	430	320	04/03/95
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	5,695,896	12/09/1997	Pierrat			12/04/95
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Examiner <i>26-2</i>	Date Considered <i>9-9-01</i>
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**Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
<u>262</u>	5,827,625	10/27/1998	Lucas, K., et al.	430	5	08/18/97
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**Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation Yes No
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<u>262</u>	Barouch, E., et al., "Vector aerial image with off-axis illumination", <u>Proceedings of SPIE, Vol. 1927, Pt. 2</u> , Optical/Laser Microlithography Conference, San Jose, CA, 686-708, (1993)
<u>262</u>	Bor, Z., et al., "New phase-shifting technique for deep UV excimer laser based lithography", <u>Proceedings of SPIE, Vol. 2380</u> , Society of Photo-Optical Instrumentation Engineers, Bellingham, WA, 195-202, (1995)
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<u>262</u>	Erdelyi, M., et al., "Enhanced microlithography using combined phase shifting and off-axis illumination", <u>Japanese Journal of Applied Physics, Part 2: Vol. 34, No. 12A</u> , L1629-L1631, (Dec. 1, 1995)
<u>262</u>	Erdelyi, M., et al., "New interferometric phase-shifting technique for sub-half-micron laser microlithography", <u>Proceedings of SPIE, Vol. 2440</u> , Society of Photo-Optical Instrumentation Engineers, Bellingham, WA, 827-37, (1995)
<u>262</u>	Ham, Y., et al., "Fundamental analysis on fabrication of 256 MB DRAM using the phase shift technology", <u>Proceedings of SPIE, Vol. 2197</u> , Optical/Laser Microlithography VII Conference, San Jose, CA, 243-52, (1994)

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9/2	Kim, K., et al., "Implementation of i-line lithography to 0.30 um design rules", <u>Proceedings of SPIE, Vol. 2440</u> , Society of Photo-Optical Instrumentation Engineers, Bellingham, WA, 76-87, (1995)
1	Levenson, M.D., "Extending optical lithography to the gigabit era", <u>Microolithography World, Vol. 3, No. 4</u> , (Autumn 1994)
	Lin, B.J., "The Attenuated Phase-Shifting Mask", <u>Solid State Technology</u> , 43-47, (January, 1992)
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	Thakar, G.V., et al., "High performance 0.3 mu m CMOS I-line lithography and BARC", <u>Digest of Technical Papers, 1995 IEEE Symposium on VLSI Technology</u> , Piscataway, NJ, 75-76, (1995)
2	Yan, P., et al., "Sub-micron low-k//1 imaging characteristics using a DUV printing tool and binary masks", <u>Proceedings of SPIE, Vol. 2440</u> , Society of Photo-Optical Instrumentation Engineers, Bellingham, WA, 270-77, (1995)

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